

## IN THE ABSTRACT

Please amend the Abstract of the Disclosure as follows:

A remote-plasma ALD apparatus includes a reaction chamber, an exhaust line for exhausting gas from the reaction chamber, a first reactive gas supply unit for selectively supplying a first reactive gas to the ~~reactionant~~ chamber or the exhaust line, a first reactive gas transfer line for connecting the first reactive gas supply unit and the ~~reactionant~~ chamber, a first bypass line for connecting the first reactive gas supply ~~unit~~line and the exhaust line, a radical supply unit for generating radicals and selectively supplying the radicals to the ~~reactionant~~ chamber or the exhaust line, a radical transfer line for connecting the radical supply unit and the ~~reactionant~~ chamber, a second bypass line for connecting the radical supply unit and the exhaust line, and a main purge gas supply unit for supplying a main purge gas to the first ~~reactiveant~~ gas transfer line and/or the radical transfer line.